

# Fabrication of Micro-cantiliver Based Sensor



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## 1. INTRODUCTION

One of the most flexible mechanical sensor systems is the microcantilever based sensor. Conventional has the limitation of having high power consumption and sensitivity, Microcantilever technology have the solutions to some of this limitations. By reducing the dimensions of the sensor to the nanometer scale, the sensor can become faster, cheaper and more sensitive. Differential stress at the surface to the beam of the cantilever causes the bending of cantilever. The cantilever bending can be detected by different read-out methods, such as optical reflection, piezoresistive, Interferometric, piezoelectric and capacitive [1-3]. In this work the direct electrical detection is used, which has an advantage of reduced complexity. Main objective towards this project is to demonstrate the application of Micro-cantilever as a temperature sensor. The design of the device is based on electrostatic actuation of a vertically deflecting cantilever and the readout method employed is electrical i.e current is used to detect the temperature. Fabrication of single layer Aluminium, Polysilicon and bi-layer cantilever (Polysilicon-Gold) and thorough electrical characterization of these sensors was done to verify the functionality of the sensor.

## 2. Microcantiliver Fabrication

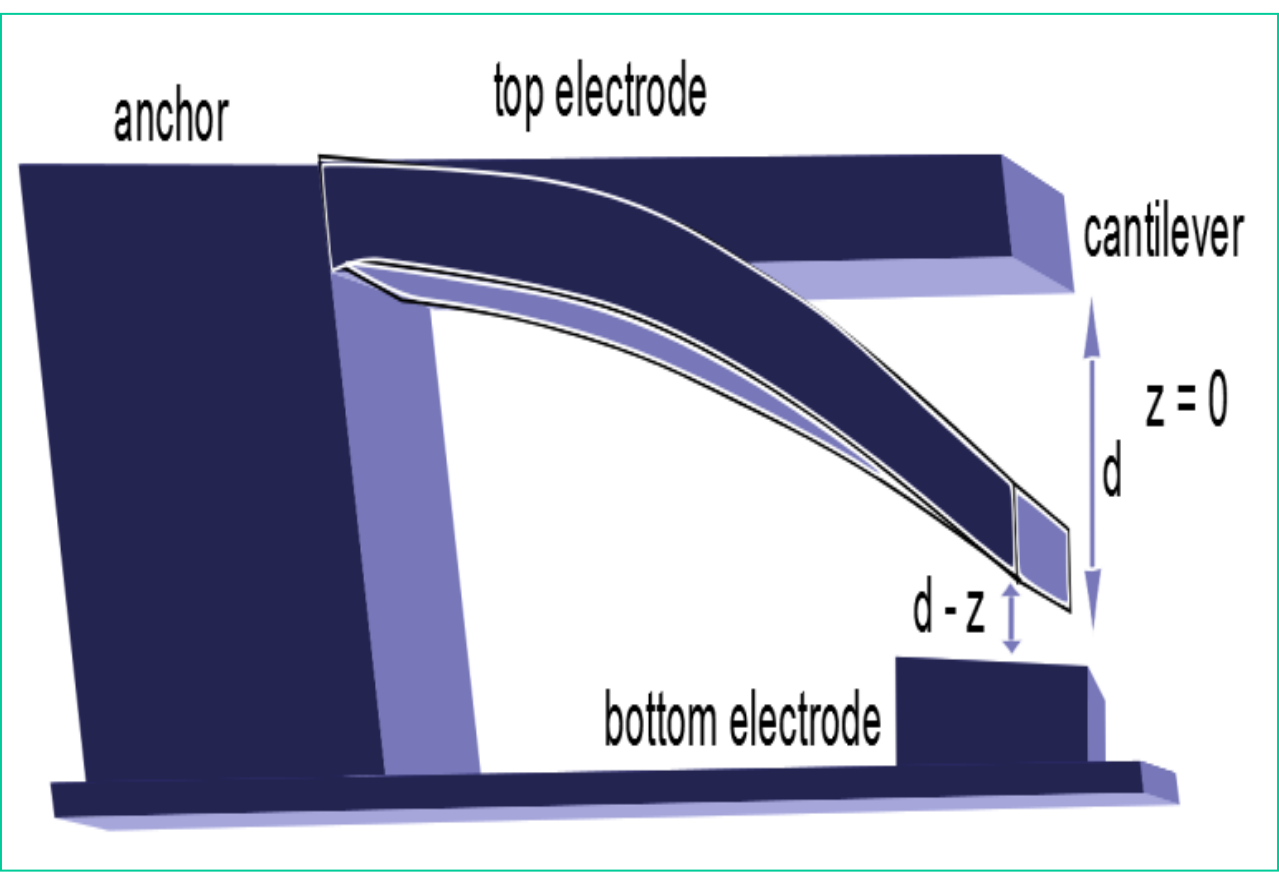


Fig.1. Microcantilever based sensor with bottom electrode

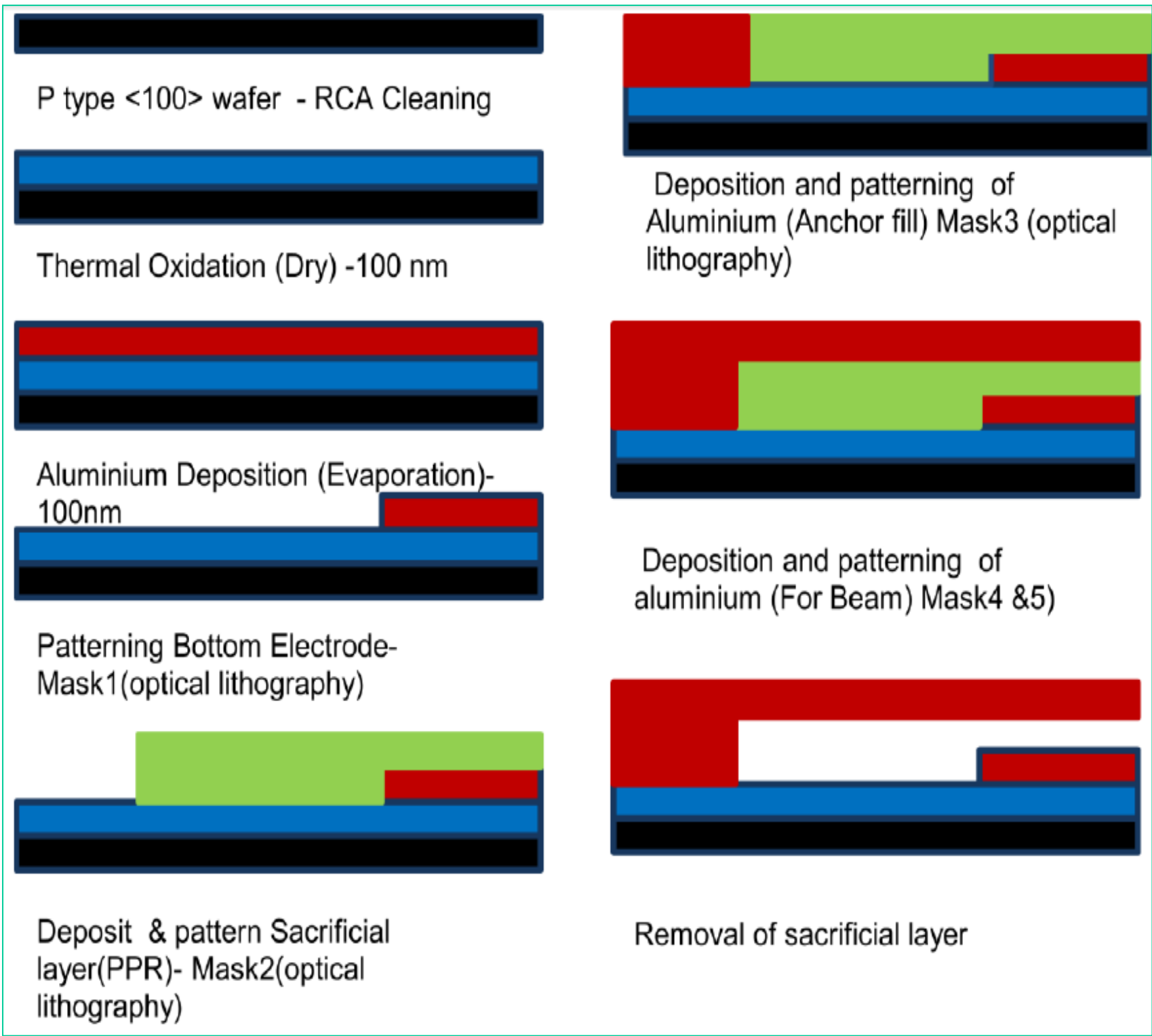


Fig.2. Process flow for Aluminium Cantilever

### A. Fabrication of Metal Cantiliver

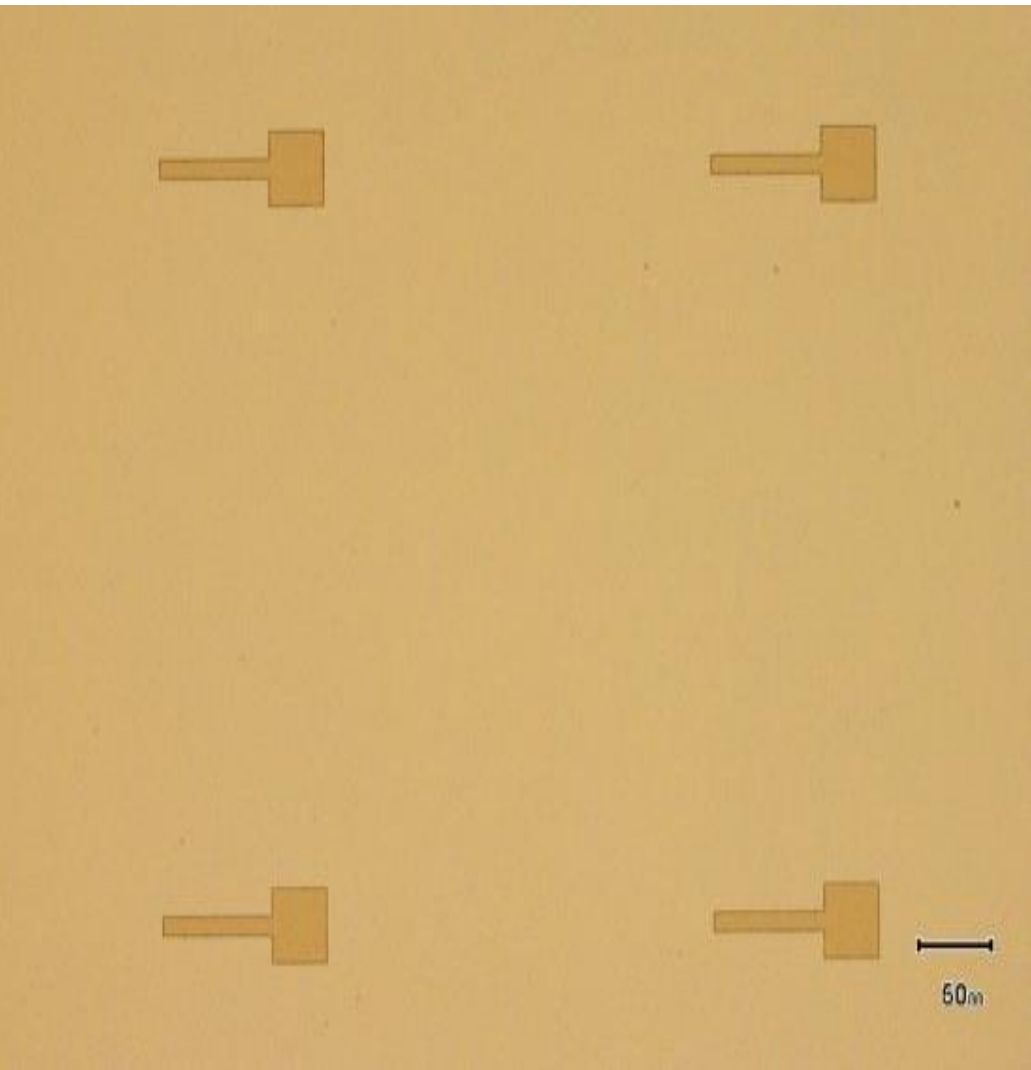


Fig.3. 1st level of Al patterning

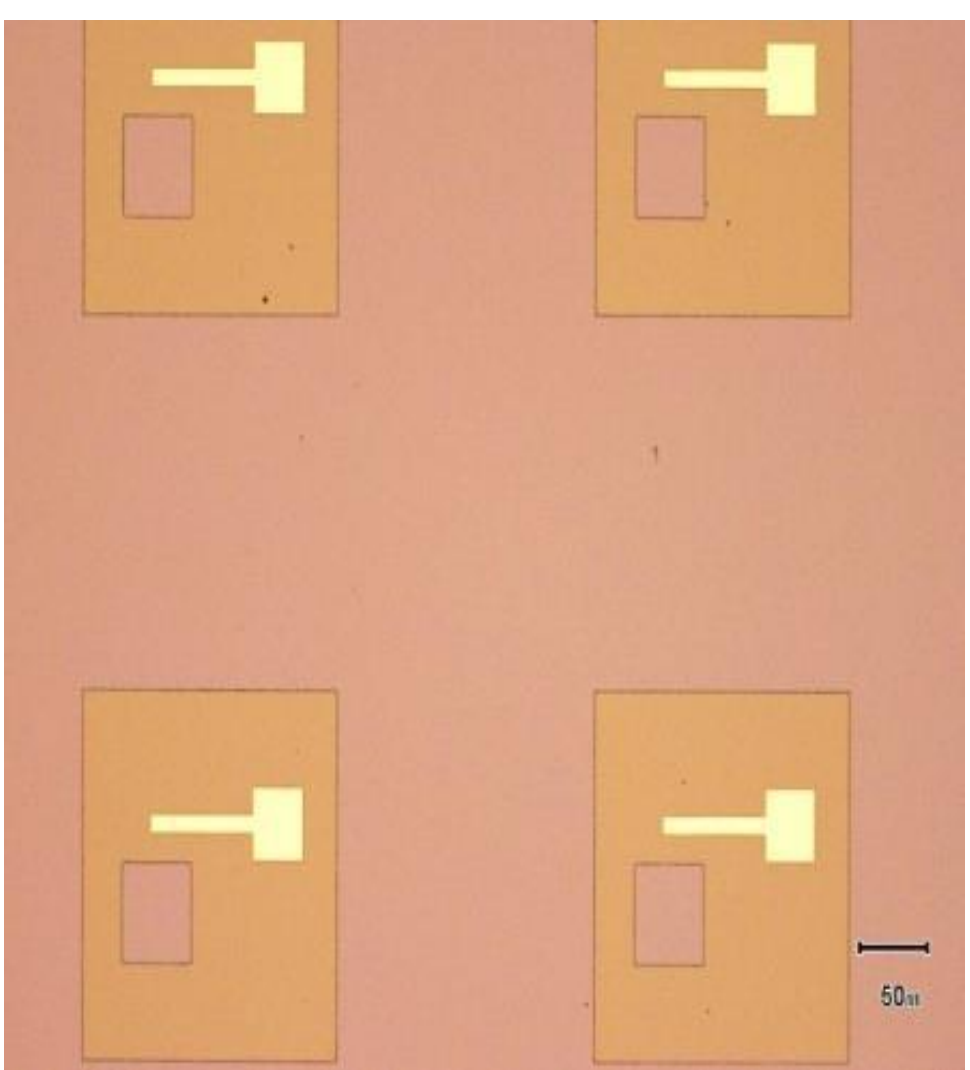


Fig.4.2nd level of S1813 resists patterning

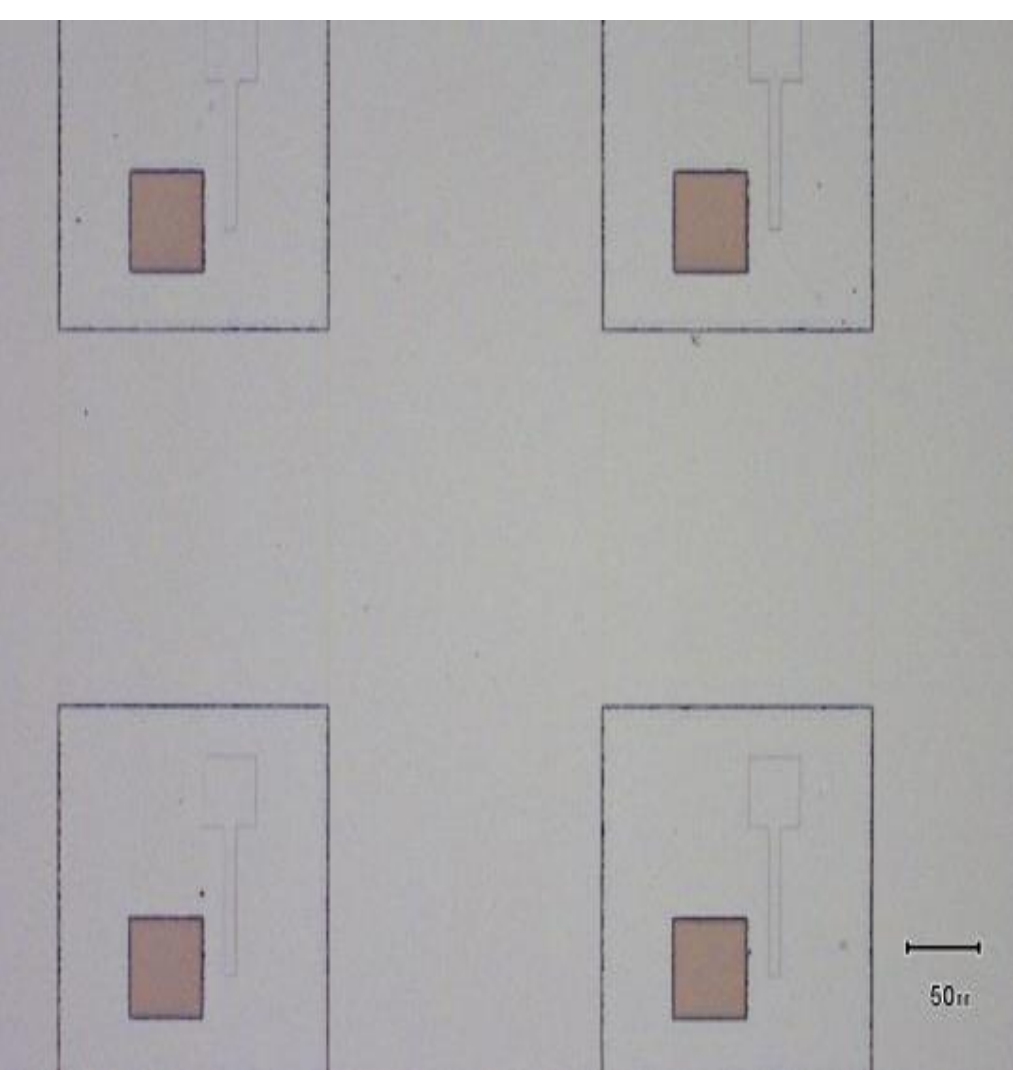


Fig.5. 3rd level of Al patterning

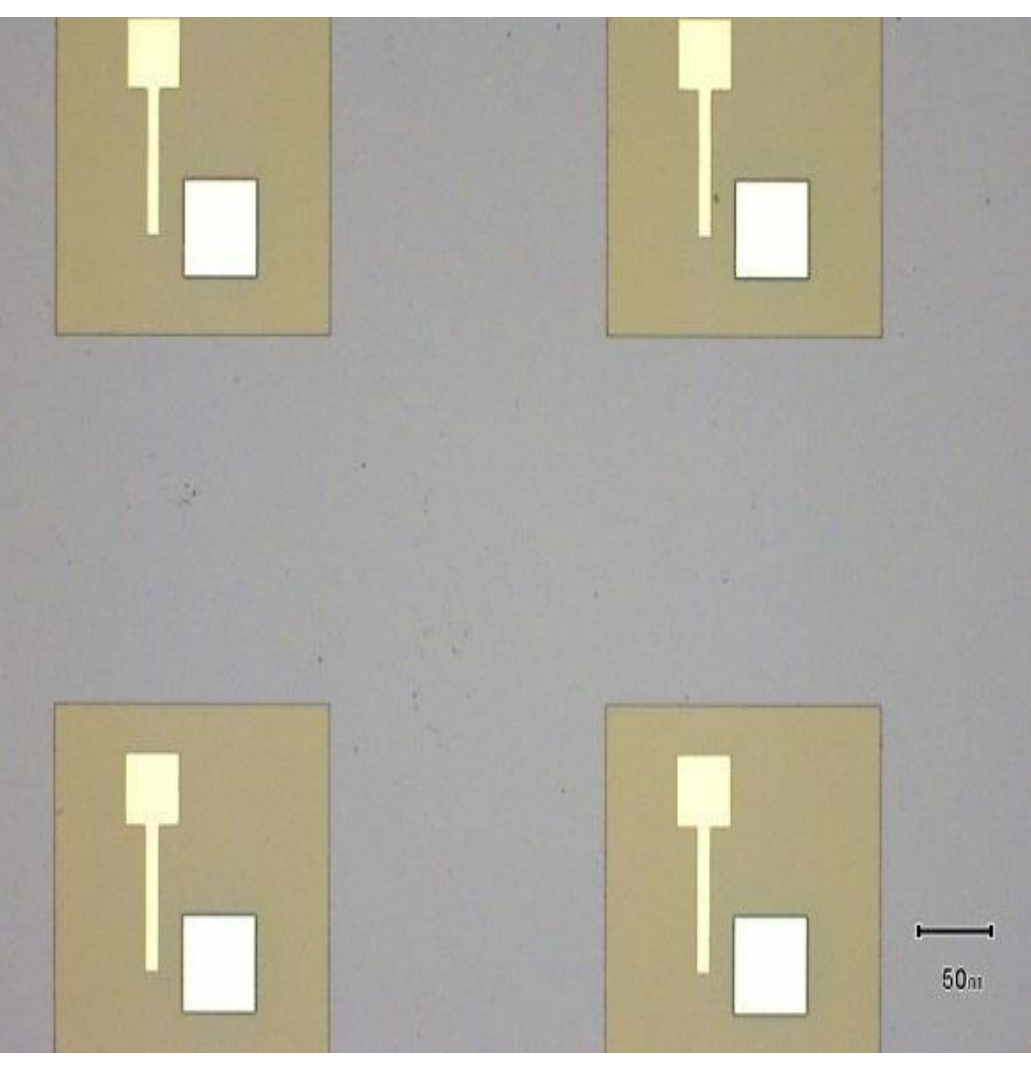


Fig.6.4th level UV Exposure and development.

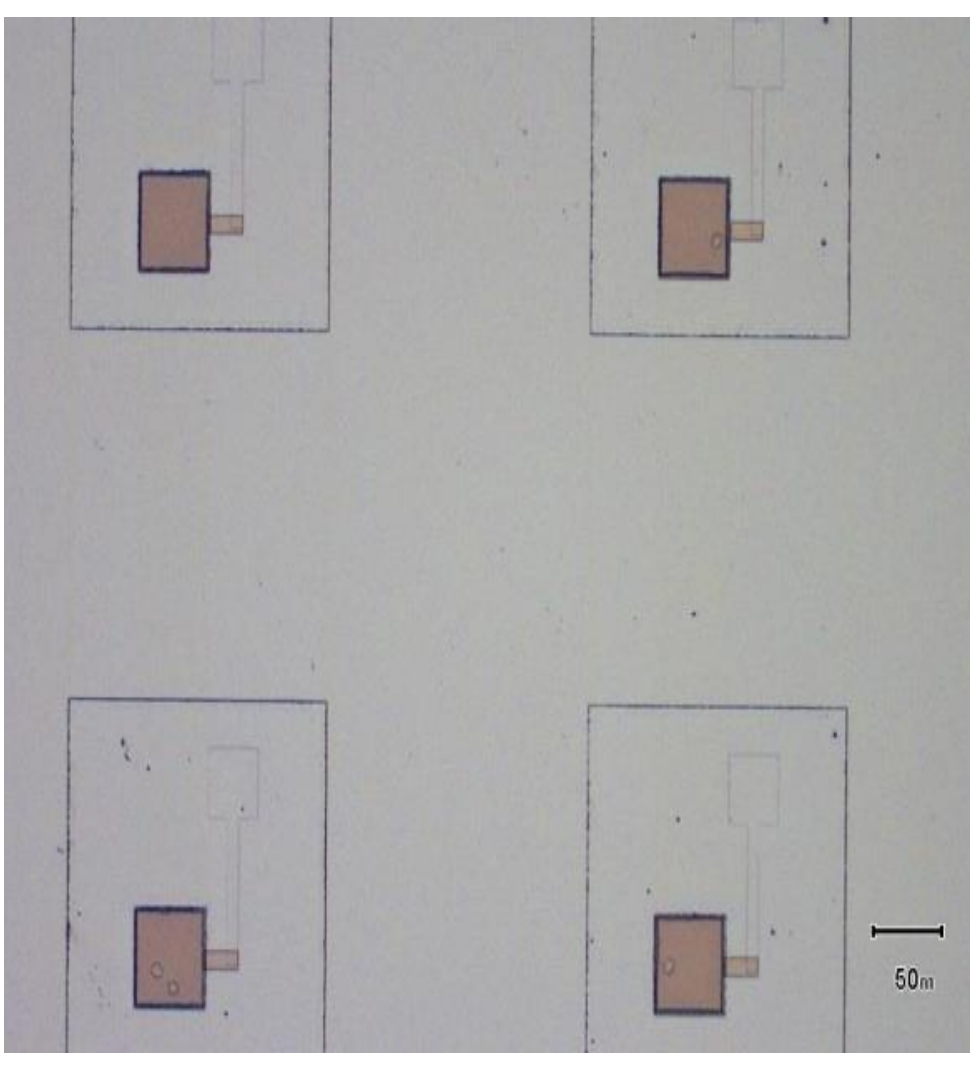


Fig.7. 5th level Al Patterning

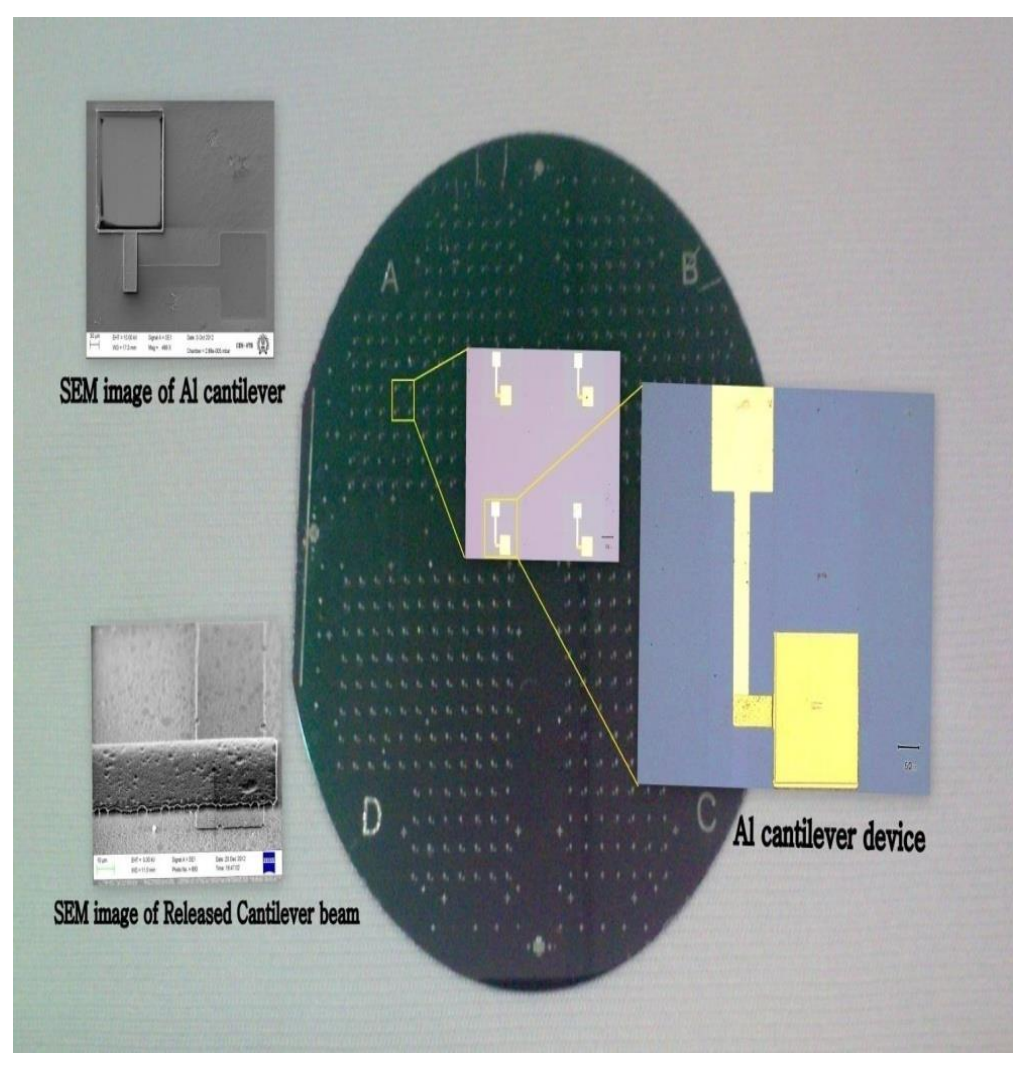


Fig.8.Fabricated microcantilevers after optimization process

### B. Images of Microcantiliver after Plasma Ashing

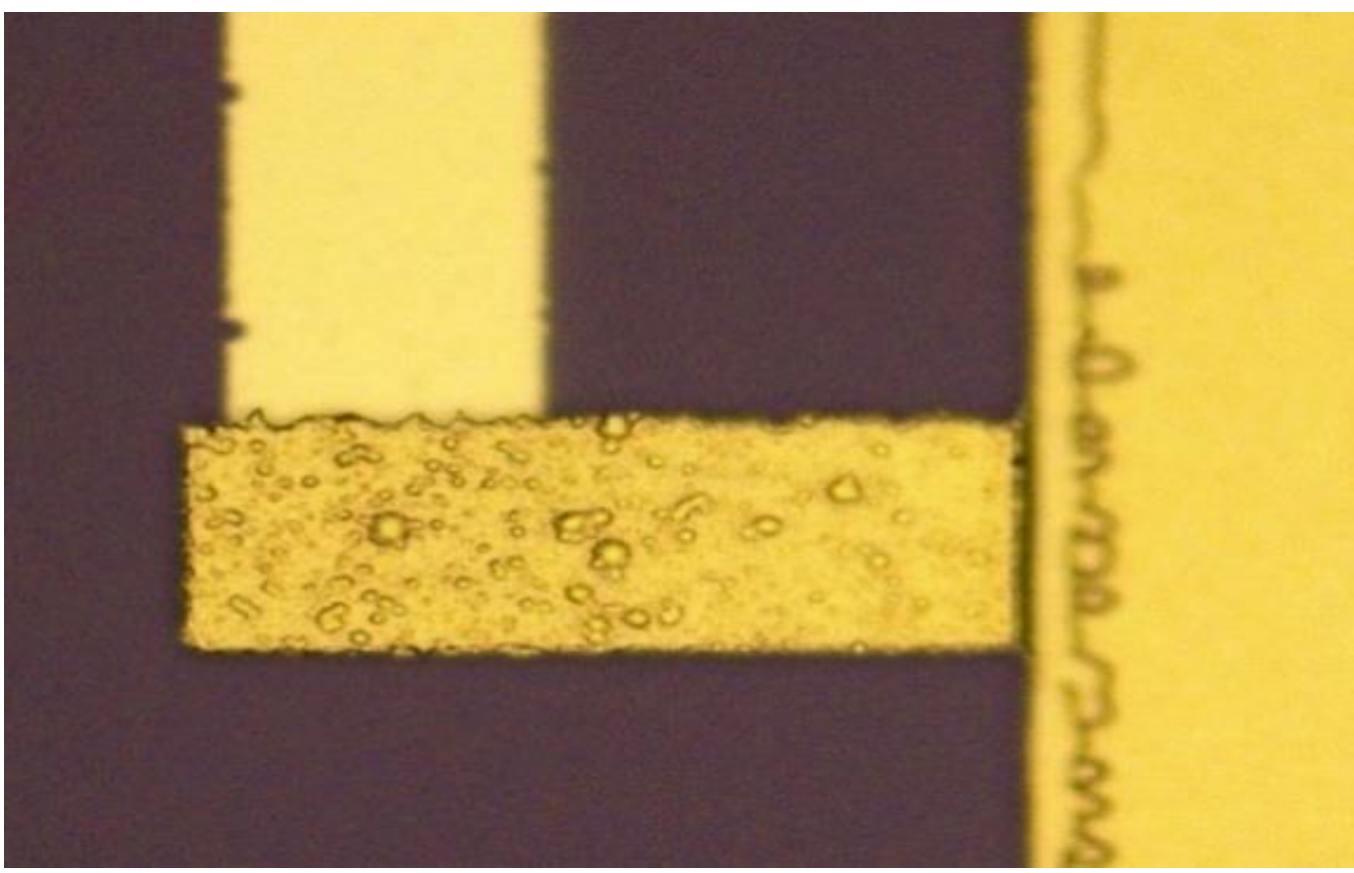


Fig.9. Surface Image

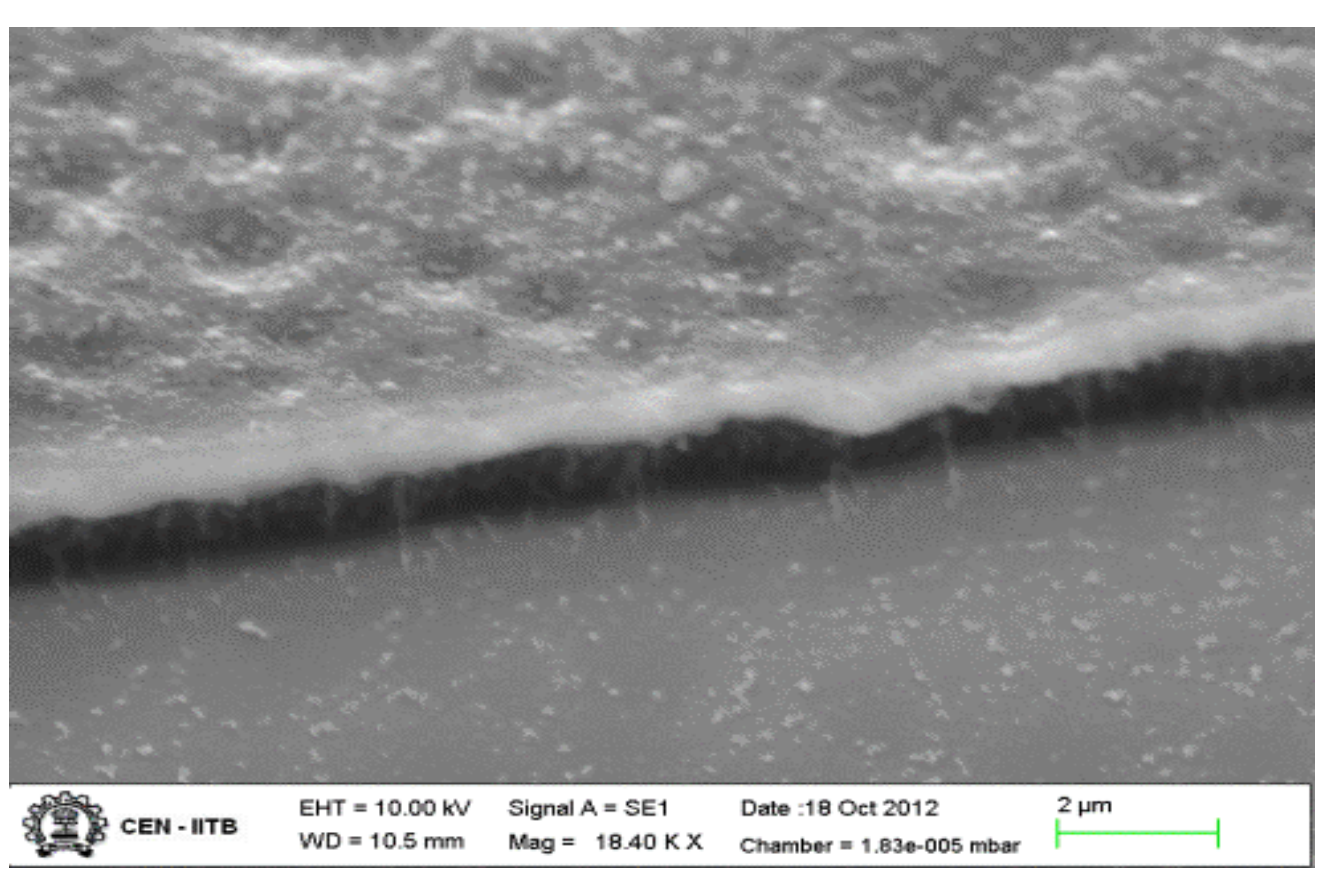


Fig.10. SEM Image

### C. Plasma Ashing at different Watts and Time Period



Fig.11.80 watt,50 sec

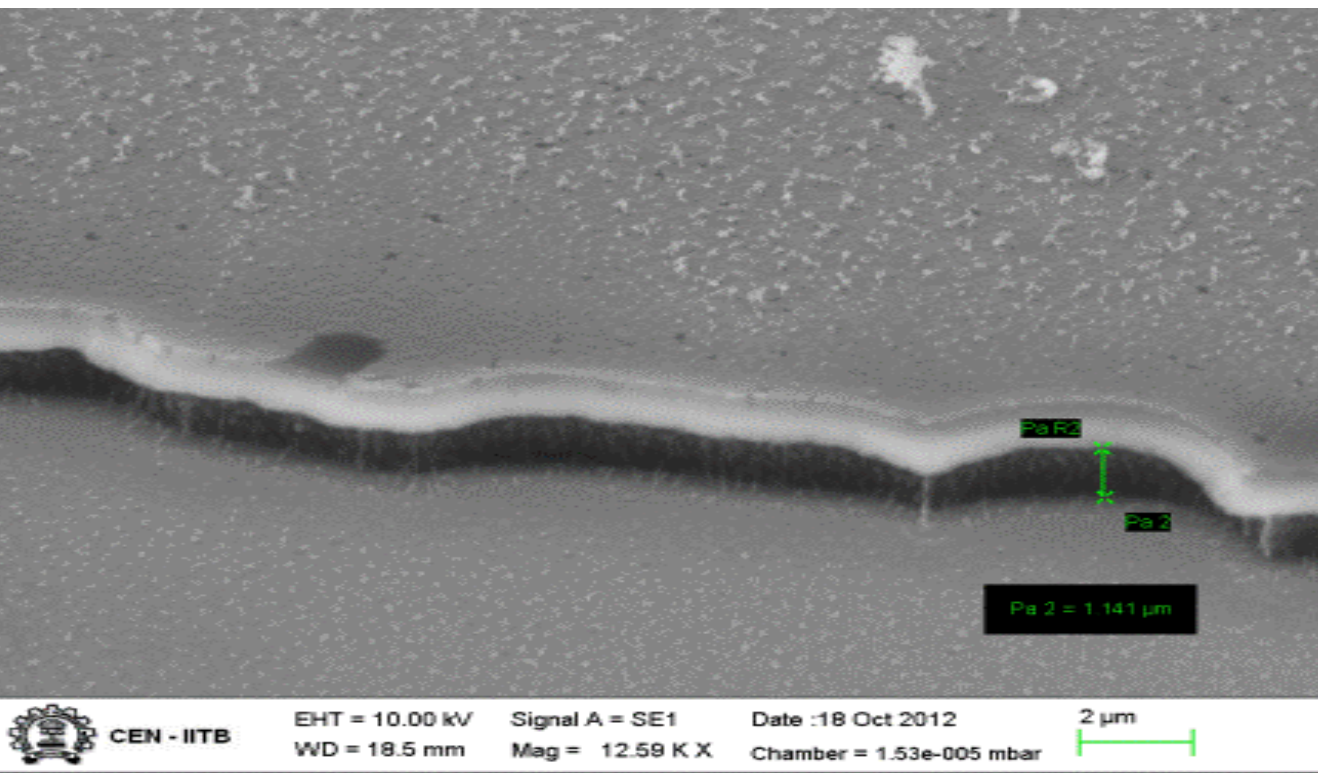


Fig.12.100watt,10min

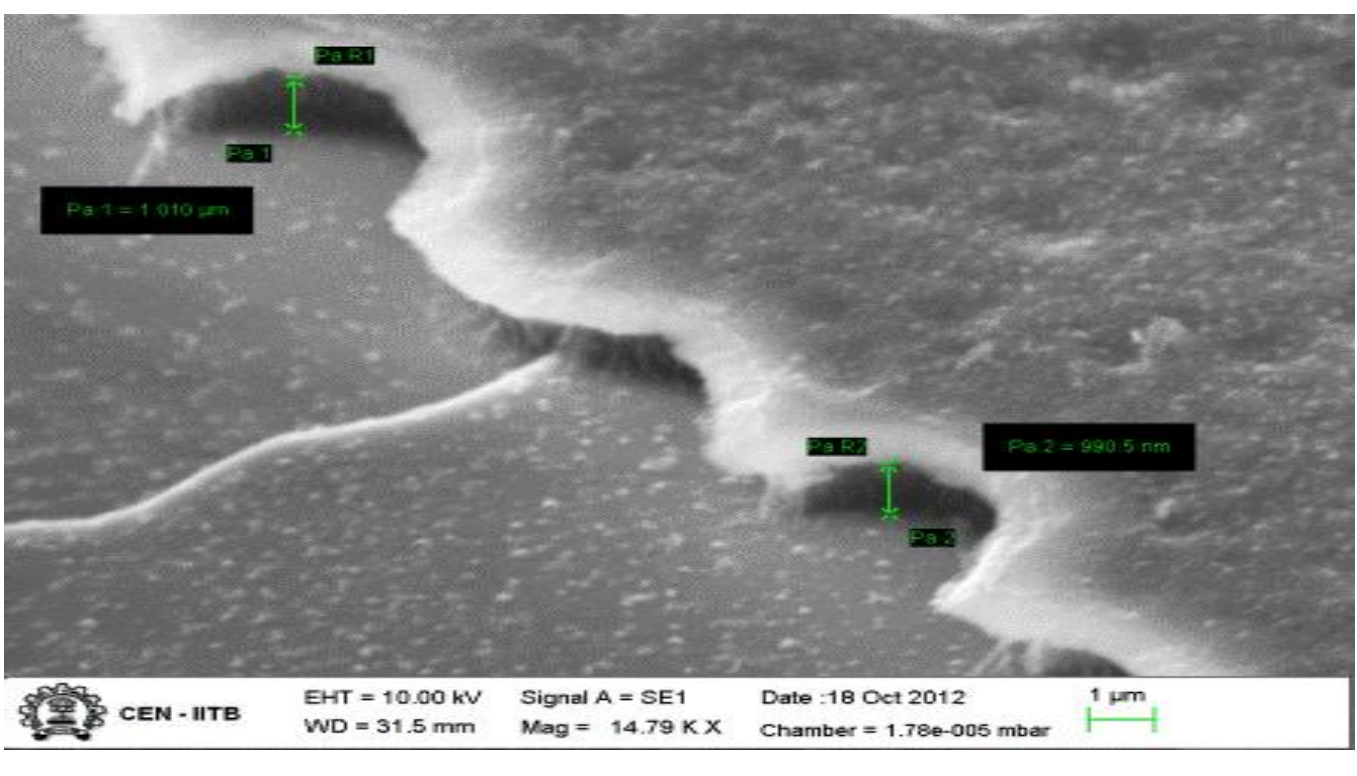


Fig.13.100watt,15 min

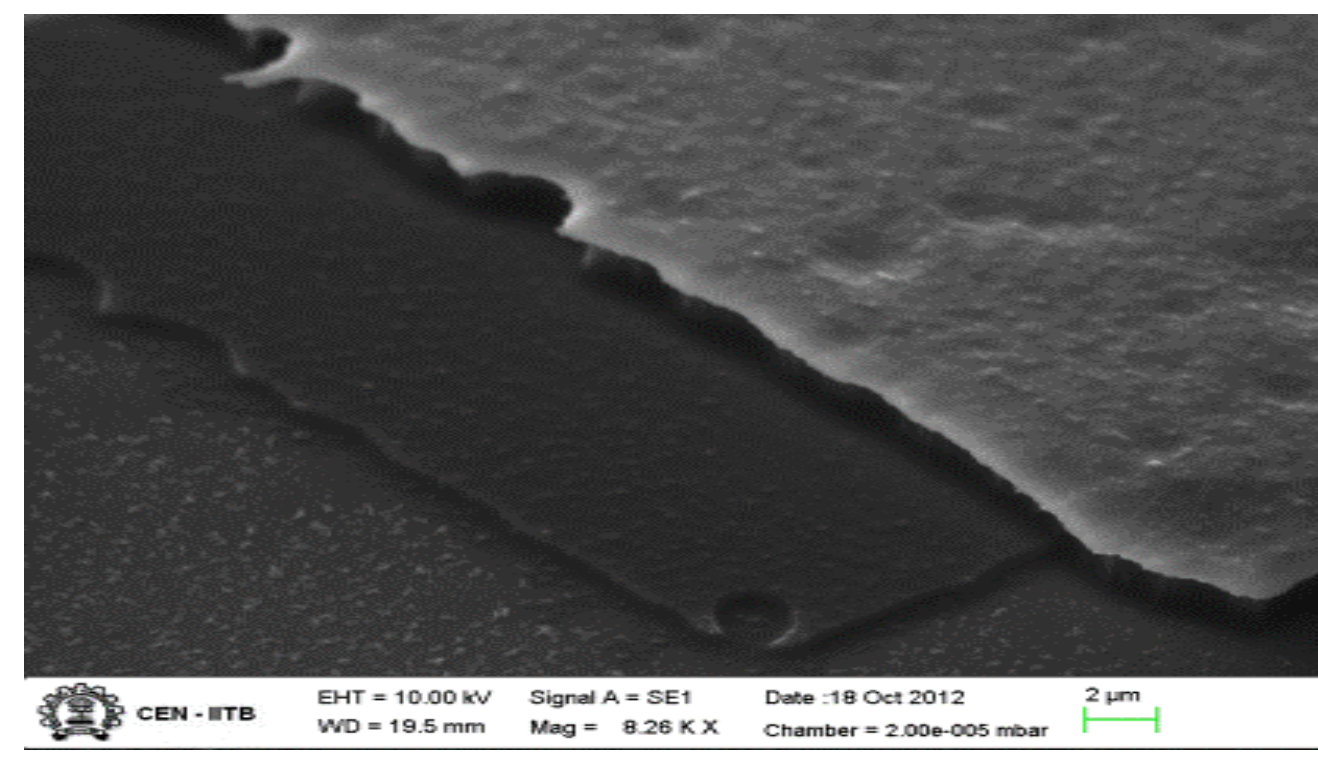


Fig.14.100 watt,30 min

## 4. Experimental Results for single layer and bi-layer cantilevers

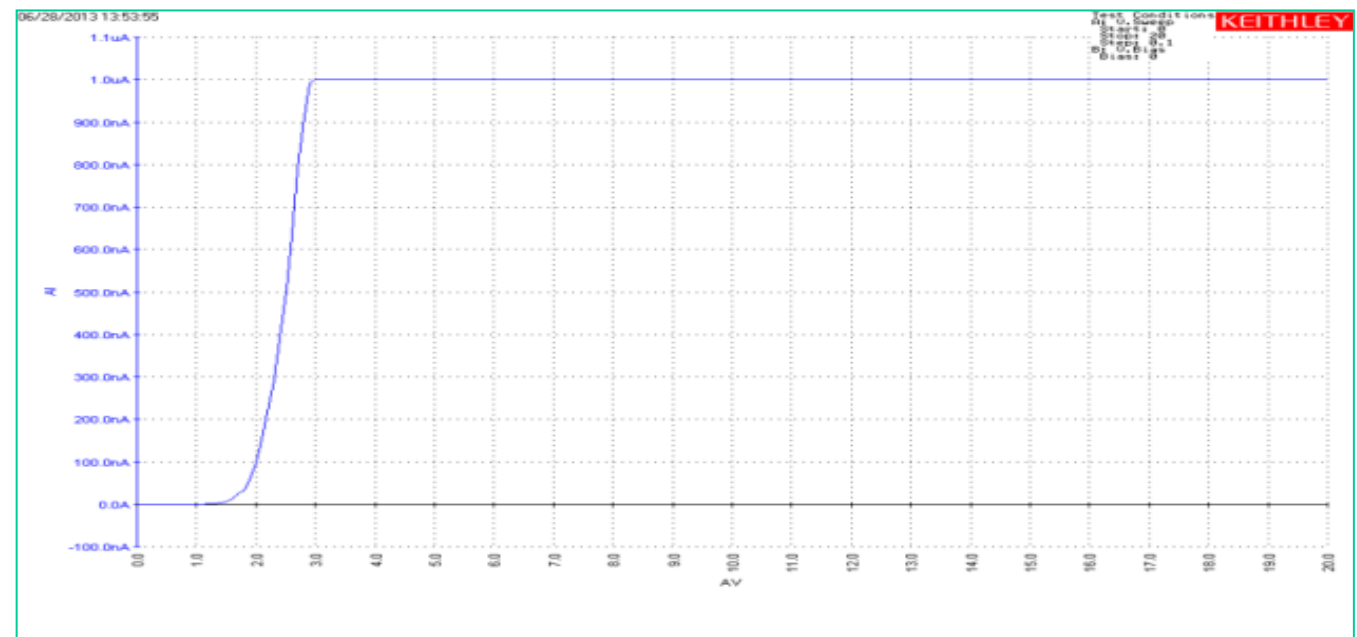


Fig.15. I-V Characterization of single layer

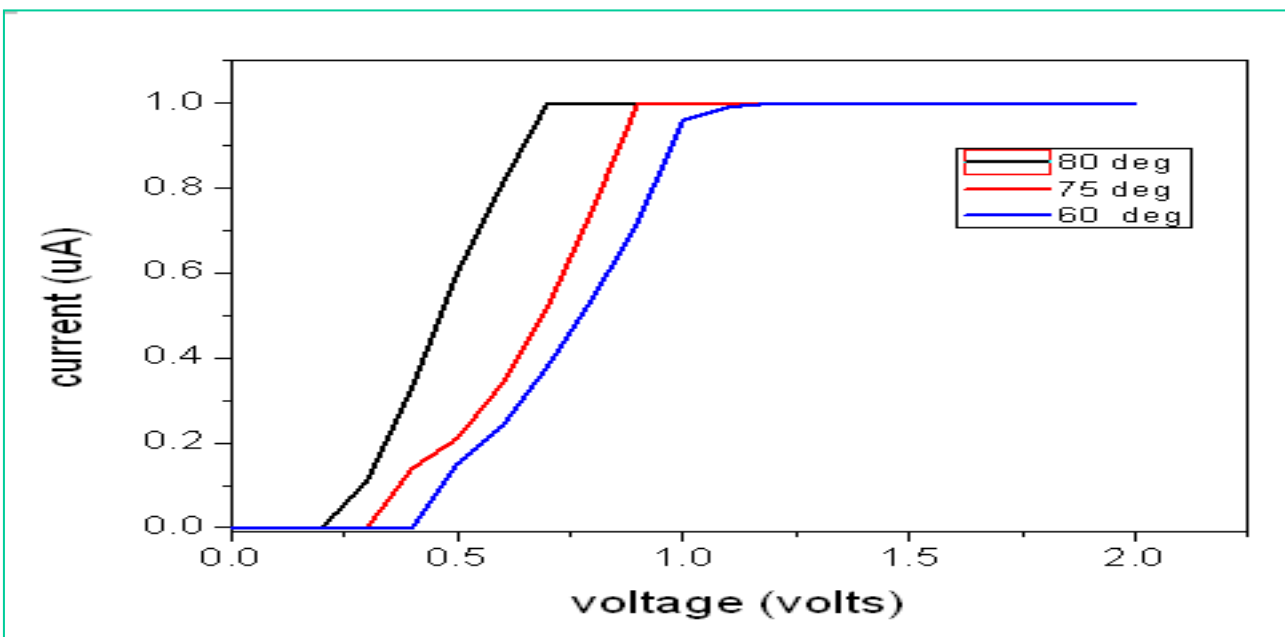


Fig.16. Temperature dependent I-V Characterization of single layer structure

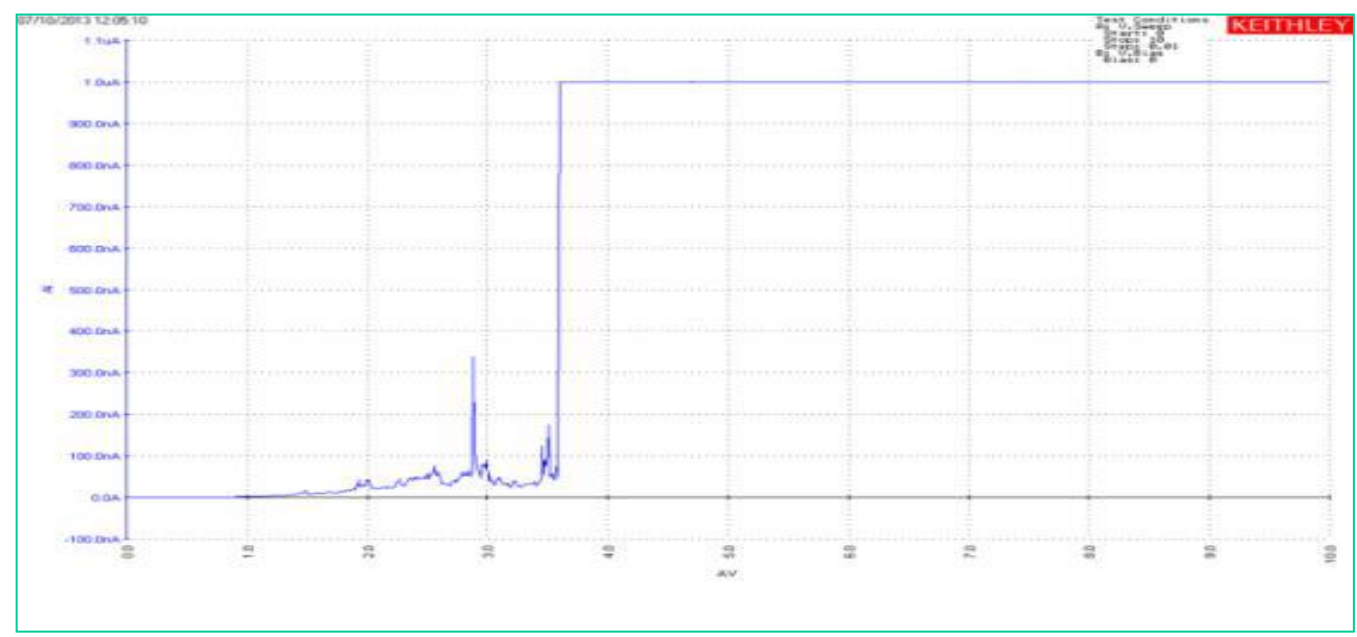


Fig.17. I-V Characterization of Bi-layer Structure

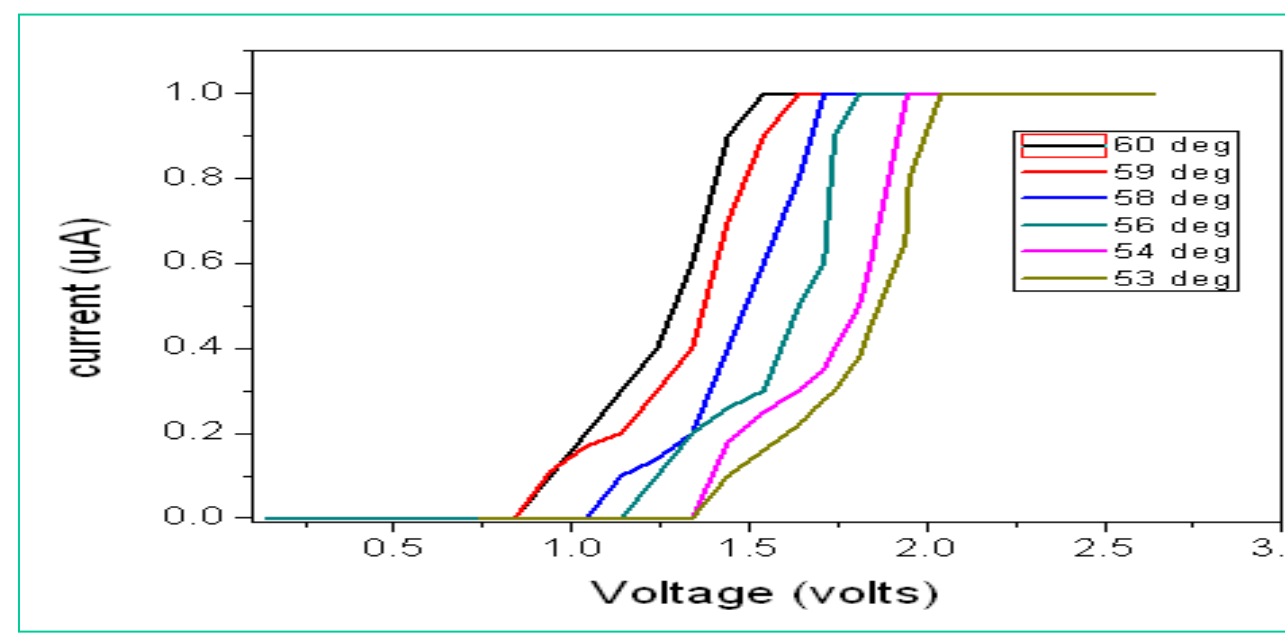


Fig.18. Temperature dependent I-V Characterization of bi-layer structure

**CONCLUSION :** In this work microcantilever sensors with electrical readout method has been designed and developed. The processes for fabrication with five step lithography were developed for each of these microcantilevers. Electrical characterization of these microcantilevers was performed. The device was prestressed with the voltage and different temperatures could be detected. Experimental results are validating the use of the microcantilever for temperature detection. The operating range for temperature sensing application is improved in bi-layer structure which is experimentally demonstrated. These measurements probably are useful in other sensors such as biosensor and accelerometer development.

### REFERENCES :

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[3] C.A. Savran, T.P. Burg, J. Fritz, and S.R. Manalis, "Microfabricated mechanical biosensor with inherently differential readout," Applied Physics Letters, vol. 83, 2003, pp. 1659-1661.

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